

| L Number | Hits | Search Text | DB | Time stamp |
|----------|---------|---|---|---------------------|
| 1 | 193095 | (low adj k) sicc sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:00 |
| 2 | 1436474 | semiconductor | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:00 |
| 3 | 6788 | silicon with (diffused diffusion duffusing diffuse) with (metal cupper cu) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:01 |
| 4 | 8283 | (si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:33 |
| 5 | 2356 | ((low adj k) sicc sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:03 |
| 6 | 27783 | diffusion with barrier | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:04 |
| 7 | 1241 | ((low adj k) sicc sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu))) and (diffusion with barrier) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:04 |
| 8 | 37526 | (etch etching etched) with (stop stopper stopped stopping) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:05 |
| 9 | 400 | ((low adj k) sicc sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu)) and (diffusion with barrier)) and ((etch etching etched) with (stop stopper stopped stopping)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:05 |
| 10 | 1094 | (si silicon) with (diffused diffusion duffusing diffuse) with (cupper cu) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 10:10 |
| 11 | 156 | ((low adj k) sicc sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu))) and (diffusion with barrier)) and ((etch etching etched) with (stop stopper stopped stopping))) and ((si silicon) with (diffused diffusion duffusing diffuse) with (cupper cu)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 09:33 |
| 12 | 2685 | (si silicon) with (diffused diffusion duffusing diffuse) with (copper cu) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 10:28 |

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|----|-----|---|---|---------------------|
| 13 | 247 | ((si silicon) with (diffused diffusion duffusing diffuse) with (copper cu)) and (((((low adj k) sicn sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu)) and (diffusion with barrier)) and ((etch etching etched) with (stop stopper stopped stopping))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 10:11 |
| 14 | 91 | ((((si silicon) with (diffused diffusion duffusing diffuse) with (copper cu)) and (((((low adj k) sicn sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu)) and (diffusion with barrier)) and ((etch etching etched) with (stop stopper stopped stopping)))) not (((((low adj k) sicn sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu)) and (diffusion with barrier)) and ((etch etching etched) with (stop stopper stopped stopping))) and ((si silicon) with (diffused diffusion duffusing diffuse) with (cupper cu))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 10:12 |
| 15 | 75 | (si silicon) adj2 (diffused diffusion duffusing diffuse) adj2 (copper cu) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 10:29 |
| 16 | 57 | ((si silicon) adj2 (diffused diffusion duffusing diffuse) adj2 (copper cu)) and ((low adj k) sicn sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/11/02 10:30 |